Exhibit 11



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(12) United States Patent Hirose

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Nov. 26, 2002 (45) Date of Patent:

(54) PLASMA PROCESSING APPARATUS

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(*) Notice: Subject to any disclaimer, the term of this

patent is extended or adjusted under 35

U.S.C. 154(b) by 0 days.

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(51) Int. Cl.⁷ H01L 21/00

U.S. Cl. 156/345.44; 156/345.47;

156/345.47; 118/723 E; 204/298.08, 298.34

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Primary Examiner—Thi Dang

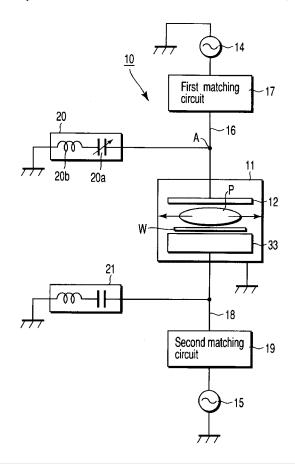
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Maier & Neustadt, P.C.

ABSTRACT (57)

The present invention concerns a plasma processing apparatus for processing a processing object by applying two types of high-frequency power with different frequencies to generate plasma. A first high-frequency line is provided with a first filter circuit for attenuating a high-frequency current from a second high-frequency power supply. A second high-frequency line is provided with a second filter circuit for attenuating a high-frequency current from a first highfrequency power supply. The first filter circuit is provided with a variable capacitor for changing a circuit constant. For changing the circuit constant, the variable capacitor is varied so that a resonance point becomes greater than an optimum resonance point most attenuating a high frequency in the second high-frequency power supply. Doing so decreases a sputter rate of the generated plasma affected on a wall surface of the processing chamber.

7 Claims, 7 Drawing Sheets





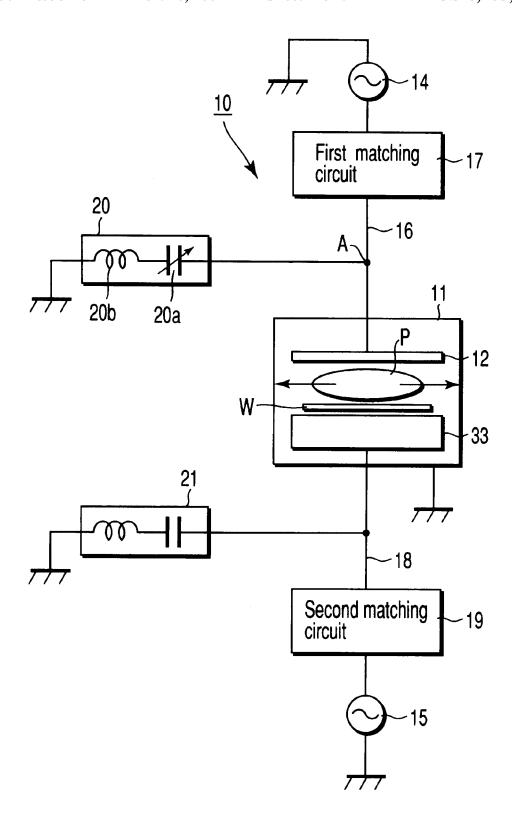
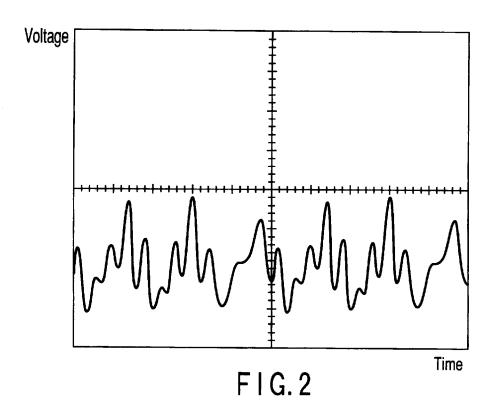
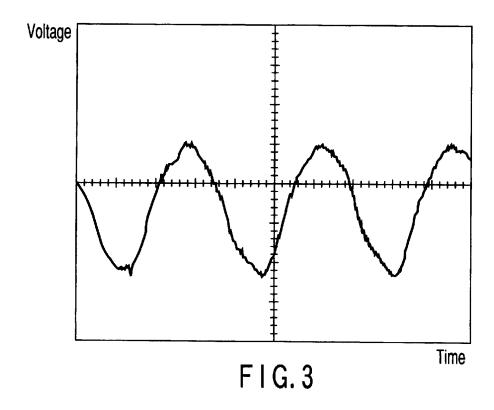


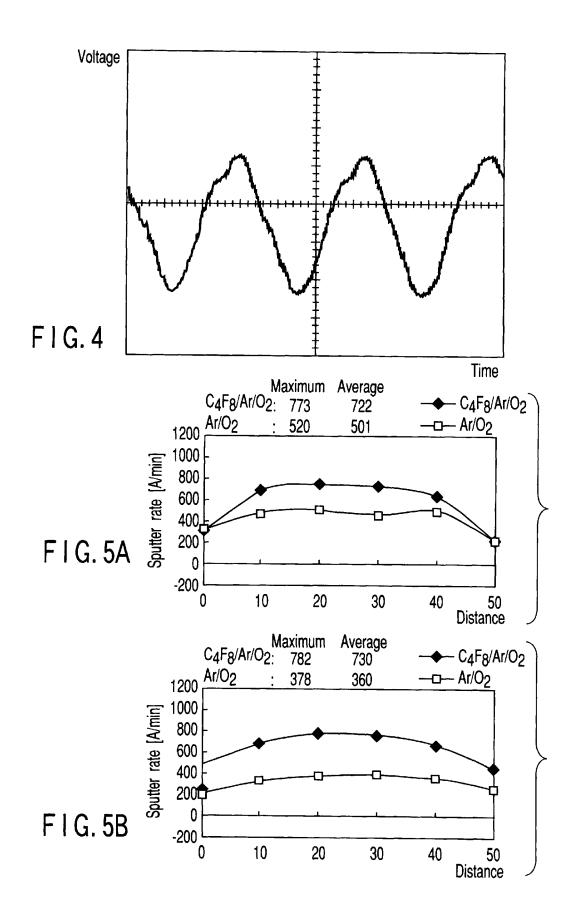
FIG.1



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